ABSTRACT

A process proximity correction method includes receiving a first layout including first to m-th regions, wherein each of the first to m-th regions include first to m-th patterns; and generating a second layout by performing machine learning-based process proximity correction based on first to n-th features the first to m-th patterns. Here, m is a natural number equal to or greater than 3 and n is a natural number greater than or equal to 2.

FIG. 2